

East Germany

VEB Werk fuer Bauelemente der Nachrichtentechnik
"Carl von Ossietzky" Berlin-Teltow. Description
of Plant, Production, and Personnel

NO. OF CASES

26 November 19
25X1

NC 100 0015

STATEMENT TO
RE: 100-100

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1. In January 1958, the official designation of the enterprise was VEB Werk fuer Bauelemente der Nachrichtentechnik "Carl von Ossietzky", Berlin-Teltow, Potsdamerstrasse 117-119. The plant, also known as the Ossietzky Werk, was subordinate to the Main Administration Radio and Telecommunications (HV RFT) of the Ministry of General Machine Construction. The plant area included a floor space of 36,000 square meters, and extended for 200 meters on Potsdamerstrasse and 180 meters on Neisserstrasse. The factory building was located on the Lichterfelde-Teltow-Stahnsdorf highway, directly at the Kleinmachnow bridge over the Teltow Canal. The plant included a production department, a testing department, and a development department. All three departments were housed in an E-shaped, 100-meter long, five-story building. Apart from this building, the plant area included a messhall, 40 meters long, and an athletics field.
2. The plant was the former Teltow VEB Dralowid (Drahtlose Widerstaende - wireless resistors) which was given its present name in 1954. The production department with a 1,500-man workforce manufactured elements for all kind of telecommunication equipment. All parts had previously been studied and tested at the development and testing department respectively. The testing department employed some 280 persons. The development department had some 175 employees including 12 scientists, 100 engineers (high-frequency specialists, mostly graduates from professional schools), and 40 technicians in addition to auxiliary personnel and administrative employees. With a view to interrupting all contacts between leading personnel of the development and testing departments and West Berlin, the Ministerium fuer Allgemeinen Maschinenbau has made repeated attempts to transfer the plant as a whole to the Polish border near Frankfurt/Oder. Transfer of individual departments was started in late 1956. As soon as a production line had been developed and tested, and serial production had been started, the department involved was transferred to the Polish border. Frankfurt/Oder and Gornsdorf near Karl-Marx-Stadt were reported as places of destination.

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CLASSIFICATION

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STATE	<input checked="" type="checkbox"/>	NAVY	<input checked="" type="checkbox"/>	NSRR		DISTRIBUTION			
ARMY	<input checked="" type="checkbox"/>	AIR	<input checked="" type="checkbox"/>	FBI					

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COUNTRY East Germany

REPORT

SUBJECT Berlin-Teltow RFT-VEB Werk fuer
 Bauelemente der Nachrichtentechnik
 (Telecommunication Elements Plant)
 Karl von Ossietzki

DATE OF REPORT 22 October 1958

PLACE ACQUIRED

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LAST REPORT ON SUBJECT
 (If applicable)

ANNEXES 1 - blueprint

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1. Prior to January 1958, the official designation of the plant under observation was RFT-VEB Werk fuer Bauelemente der Nachrichtentechnik Carl von Ossietzki, Ministerium fuer den Allgemeinen Maschinenbau, HV RFT, Ossietzki. It was located on 117-119 Potsdamerstrasse in Teltow near Berlin. The plant area covered a floor space of 36,000 m², with a 200-meter front along Potsdamerstrasse and a 180-meter front along Neissestrasse. The factory building was located on the Lichterfelde-Teltow-Stahnsdorf highway, directly at the Kleinmachnow bridge over the Teltow Canal. The plant included a production department, a testing department, and a development department. All three departments were housed in an E-shaped, 100-meter long, five-story building. Apart from the abovementioned building, the plant area included a messhall, 40 meters long, and an athletics field.
2. The plant was the former Teltow VEB Dralowid (Drähtlose Widerstaende - wireless resistors) which was given its present name in 1954. The production department with a 1,500-men workforce manufactured elements for all kind of telecommunication equipment. All parts had previously been studied and tested at the development and testing department respectively. The testing department employed some 280 persons. The development department had some 175 employees including 12 scientists, 100 engineers (high-frequency specialists, mostly graduates from professional schools), and 40 technicians in addition to auxiliary personnel and administrative employees. With a view to interrupting all contacts between leading personnel of the development and testing departments and West Berlin, the Ministerium fuer Allgemeinen Maschinenbau has made repeated attempts to transfer the plant as a whole to the Polish border near Frankfurt/Oder. Transfer of individual departments was started in late 1956. As soon as a production line had been developed and tested, and serial production had been started, the department involved was transferred to the Polish border. Frankfurt/Oder and Gornsdorf near Chemnitz were reported as places of destination.

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3. Work was being stepped up in the field of semiconductors, particularly the development of germanium and silicon transistors, both point transistors and plate transistors, as well as junction-type diodes and germanium and silicon diodes. The aim was to reach US standards. For this purpose a sum of 5 to 6 million DME had been made available to the development department for 1958. Progress was retarded by inadequate production of high-purity germanium and silicon, although satisfactory results were reached in recent times. Under US patents pure germanium and silicon have already successfully been used. Another stepped-up line was the development of resistors and magnetic material. Special attention was being paid to boron-carbon deposited resistors in view of their high constancy, capacitance, and low temperature coefficient. Efforts were also made to develop water-cooled, 1-100 kW antenna resistors, extra-high tension resistors of up to 200,000 V, and d.c.-resistant film resistors. A total of 1,500,000 DME were earmarked for these fields of investigation under the 1958 plan.
4. The plant was expected to fulfill its 1958 planned output of 90 million resistors, several million diodes, and some 100,000 transistors.
5. The products were delivered in the first place to Berlin-Koepenick, Leipzig, Erfurt, Radeberg (VEB Rafena), Sonneberg (Stern-Radio), and Berlin-Weissensee (Stern-Radio). Exports were shipped to China, the Soviet Union, Hungary, Poland, Czechoslovakia, and the [redacted] (Berlin Telefunkenwerke). The exports were handled by DIA Elektrotechnik, located on Tucholskistrasse in Berlin.

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6. The following personnel was reported for the individual departments:

- a. Production Department

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Manager	Bohrmann
Cadre chief	Gossmann, Erna
BPO (factory party organization) chief	Krusch
BGL (factory union local) chief	Thurley
Labor chief	Roeppke
Commercial manager	Hermann Ewert
Technical manager	Friederici
Production manager	Leonhardt
Chief of film resistor department	Leonhardt
Chief of iron powder core department	Walter Goetze

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Chief of infrared emitter department (this department was slated for transfer to Oranienburg with its 150-men workforce)

undetermined

Chief of wire-wound resistor department (this department was transferred to Gornsdorf near Chemnitz with a 180-men workforce in October 1957)

undetermined

Chief of "Panta-Chm" department (vitreous enamel-coated and cemented wire-wound resistors) (this department was transferred to Gornsdorf near Chemnitz with a 100-men workforce in October 1957)

undetermined

Chief of diode department (this department was transferred to Frankfurt/Oder with a 180-men workforce in December 1957)

undetermined

Chief of potentiometer department (this department was transferred to Gornsdorf near Chemnitz with a 100-men workforce in November 1957)

undetermined.

b. Development Department

Manager	Dr. Matthias Falter
Deputy	Dr.ing. Henninger
Secretary	Philomena Schmidt
Scientific assistant	Reabe
Chief of semiconductor main department	Dr. Blankenburg
Chief of resistor and magnetic materials main department	Dr. Henninger
Film resistor laboratory	15 workers
Iron powder core and ferrite laboratory	10 workers
Fixed composition resistor laboratory	5 workers
Infrared emitter laboratory	4 workers

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Potentiometer and colloidal resistor laboratory	3 workers
Transistor laboratory	12 "
Diode laboratory	10 "
Plate diode laboratory	8 "
Fundamental research laboratory	12 "
Crystal laboratory	4 "
Application laboratory	4 "
Metal deposit laboratory	4 "
Hot-conductor laboratory	8 "
Construction office	----
Construction office Lange	8 "
Construction office Seidelmann	6 "
Chemical laboratory	10 "
Glass laboratory	4 "
Mechanical testing laboratory	20 "
Electromechanical testing laboratory	10 "
Blue print shop	3 "
Photographic laboratory	3 "

About two-thirds of all efforts were dedicated to development work in the main department for semiconductors, the remaining one-third to work in the main department for resistors and magnetic material matters.

c. Testing Department

Manager	Jaszc
Chief of semiconductor main department	Guenther Schmidt
Chief of resistor and magnetic materials main department	Alfred Meister

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Resistor department	15 workers
Iron powder core, ferrite, and carbonyl-iron core department	12 workers
Potentiometer department	4 workers
Diode department	50 workers
Transistor department	50 workers
Plate diode department	20 workers
Planning department	10 workers
Preparation department	10 workers
Commercial department	50 workers
Library	3 workers.

Comment. For diagram showing the organization of
RFT-VEB Werk fuer Bauelemente der Nachrichtentechnik
"Karl von Ossietzki", Berlin-Teltow, see Annex.

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Struktur-Skizze

"RFT/VBB Werk für Bauelemente
der Nachrichtentechnik,
Carl von Ossietzky,
T.E.I.T.O.W. bei BERLIN,
Stand: Januar 1958.

Anlage zu:

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